

Applicants hereby provisionally elect the Group III claims with traverse. Applicants respectfully submit that the Restriction Requirement is improper for the following reasons.

Since the four groups of claims relate to circuits or circuit elements that are made using aperture masks, the searches required will be substantially the same for each group. A search for the deposition method should also produce references concerning the deposition system, and integrated circuits and transistors made using aperture mask deposition techniques. Searching the four groups for a single patent application thus should not present an extra burden for the PTO.

Even if the Restriction Requirement is maintained, Applicants believe that Groups I, III, and IV should be combined into one group since they are all classified in the same class (Class 257). At a minimum, Applicants believe that Groups III and IV should be combined into one group since integrated circuits often comprise transistors linked together by electrical connections. A search for circuits made using aperture mask deposition should also produce references concerning circuit elements made using aperture mask deposition. Applicants therefore respectfully request reconsideration (and withdrawal or at least modification) of the Restriction Requirement.

Registration Number 32,834	Telephone Number 651-733-1189
Date <i>January 6, 2003</i>	

Respectfully submitted,

By

Lacy C. Weiss
Lacy C. Weiss

Office of Intellectual Property Counsel
3M Innovative Properties Company
P.O. Box 33427
St. Paul, Minnesota 55133-3427
Facsimile: (651) 736-3833

P:\thomplisa\57181\57181US002 res req.doc

FAX RECEIVED

JAN 06 2003

TECHNOLOGY CENTER 2800